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PATENT ABSTRACTS OF JAPAN

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H01L 21/285

(21)Application number : 09-060377 (71)Applicant : UNITED MICROELECTRON CORP

(22)Date of filing : 14.03.1997 (72)Inventor : GO KONRIN
RO KOHAKU
LIN JENN-TARNG

(30)Priority

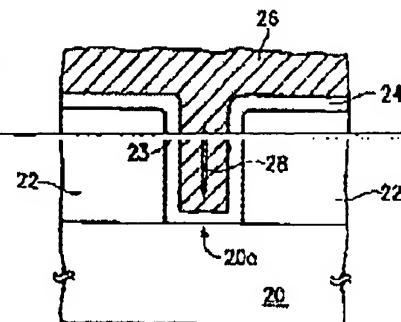
Priority number : 96 85110947 Priority date : 07.09.1996 Priority country : TW

(54) MANUFACTURE OF CONDUCTIVE PLUG

(57)Abstract:

PROBLEM TO BE SOLVED: To prevent the generation of voids in a conductive plug and to prevent the resistance value of the plug from being increased by a method, wherein a diffusion barrier layer is formed on an exposed conductive region and the peripheral part of a contact window and a hydrogen plasma treatment is performed to fill a conductive material in the contact window.

SOLUTION: A diffusion barrier layer 24 is formed on a region 20a made of a conductive material, the periphery of a contact window 23 and the upper surface of an insulating layer 22 and a hydrogen plasma treatment is performed on the conditions of power of 3000W or lower, a hydrogen flow rate of 3000sccm or lower, a reaction temperature of 1000°C or lower and 10-second to 10-minute reaction intervals. A conductive material 26, such as tungsten, is filled in the window 23 by a PVD or the like and a conductive plug having the smallest void 28 is formed. Accordingly, the problem of the generation of voids is dissolved, and the contact resistance value of the plug can be reduced.



Searching PAJ

페이지 2 / 2

LEGAL STATUS

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獨立請求	未請求	請求項の數12	①1. 外國語出版 (全 10 頁)
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(71) 華人 544162X04

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(33) 續完他主型(1) 台灣 (TW)

(72) 我 們 已 經 知 道

台灣台中市台中港路二段98之18號

(72) 地 點 處 於 柏

台灣新竹市民第一例 8 熱 16 號

(7) 代理人 弁護士 磯野 道治

最終的に

(50) (6.4.2) 名詞 名詞の活用形。

157 (344)

【註 36】 定数 β の導出法を附示する。

0.27% = 1.1%。これは、同様に、心臓のポンプ機能が正常に保たれていることを示す。心臓のポンプ機能が正常に保たれていることは、心臓のポンプ機能が正常に保たれていることを示す。心臓のポンプ機能が正常に保たれていることは、心臓のポンプ機能が正常に保たれていることを示す。

